



IBW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: David Skee
Serial No. 10/572,860
Title: ALKALINE, POST PLASMA ETCH/ASH RESIDUE REMOVERS AND
PHOTORESIST STRIPPING COMPOSITIONS CONTAINING METAL-
HALIDE CORROSION INHIBITORS
Filed: February 23, 2006
Examiner: 1796
Confirmation No.: 3653
Customer No.: 24,289
Attorney Docket No.: 1595 WO/US

MAIL STOP: AMENDMENT

Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION

Honorable Commissioner for Patents:

The Office Action of March 23, 2009 has required restriction between the following two groups of claims on the contention that they are separate and distinct inventions.

Group I: Claims 1, 2, 5-7, 10, 13, 19 and 20 drawn to compositions, and

Group II: Claims 25, 26, 29-31, 34, 37, 41, 43 and 44 drawn to the use of those compositions to clean semiconductors.

It is respectfully submitted that this restriction requirement is improper. The inventions are not separate and distinct as alleged, but are instead drawn to a single invention of compositions suitable for cleaning microelectronic substrates.. The Office Action alleges that the compositions of group I claims may be used to etch glass, clean glass or as a dental treatment. These contentions are without any substantive basis or technical support and are mere unwarranted speculations. It is respectfully submitted that the claimed compositions will not have those uses